

Cobalt and Manganese Carboxylates for Metal Oxide Thin Film Deposition by Applying the Atmospheric Pressure Combustion Chemical Vapour Deposition Process

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Wire-firm model of complex 5

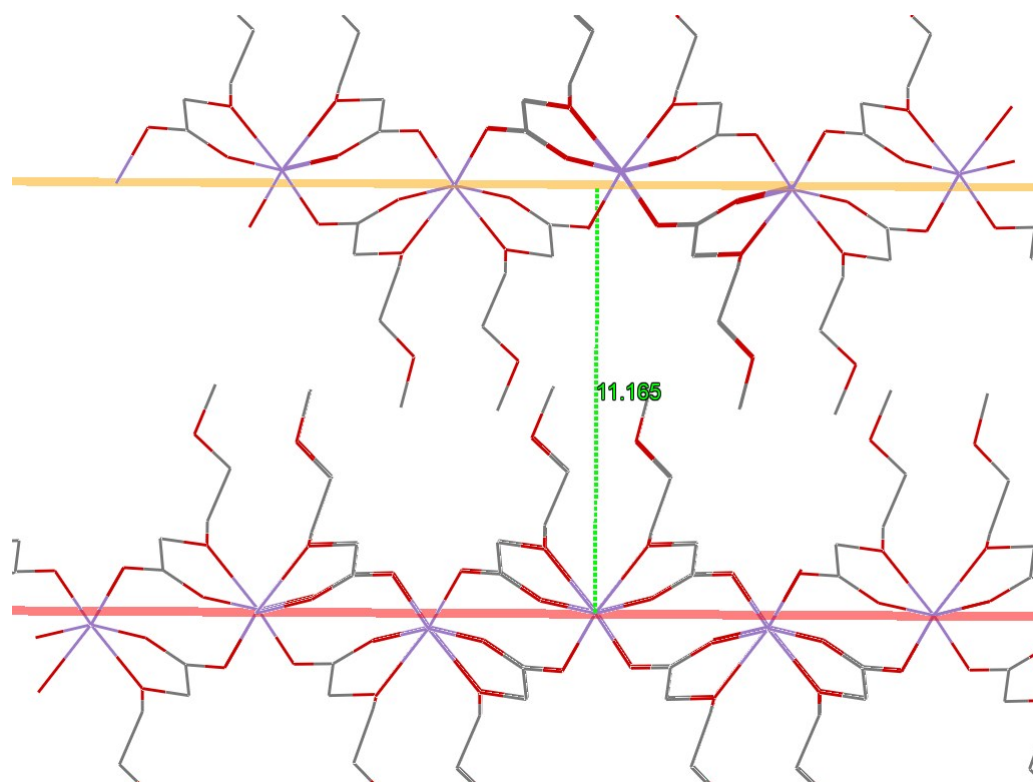


Figure S11. Wire-firm model of complex 5 showing the distance of 11.165 nm between manganese atoms of adjacent layers.

PXRD patterns of the TG residues

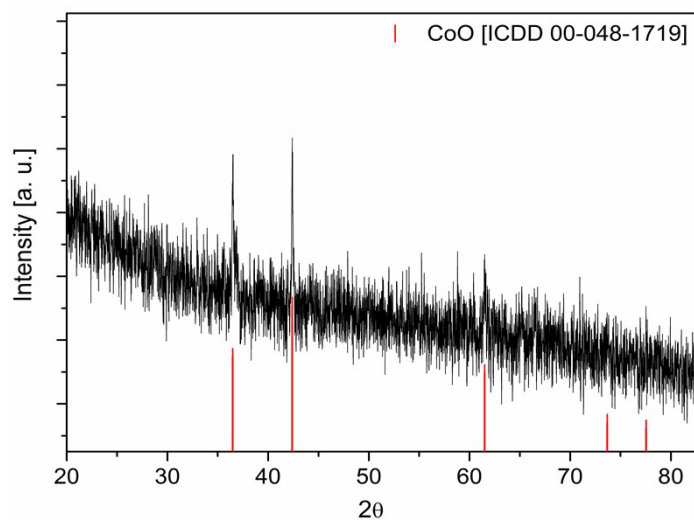


Figure SI2. PXRD of the residue obtained by the TG-MS study of **4** under argon (gas flow, 60 mL; heating rate, 5 K min⁻¹).

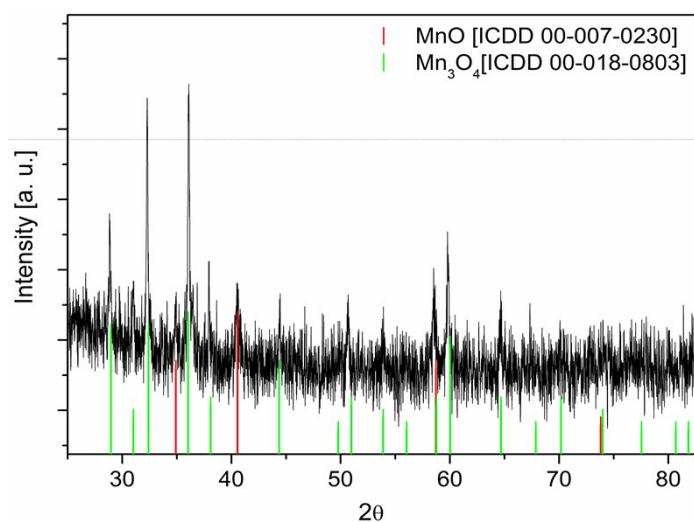


Figure SI3. PXRD of the residue obtained by the TG-MS study of **5** under argon (gas flow, 60 mL; heating rate, 2.5 K min⁻¹).

XPS patterns of the deposited thin films

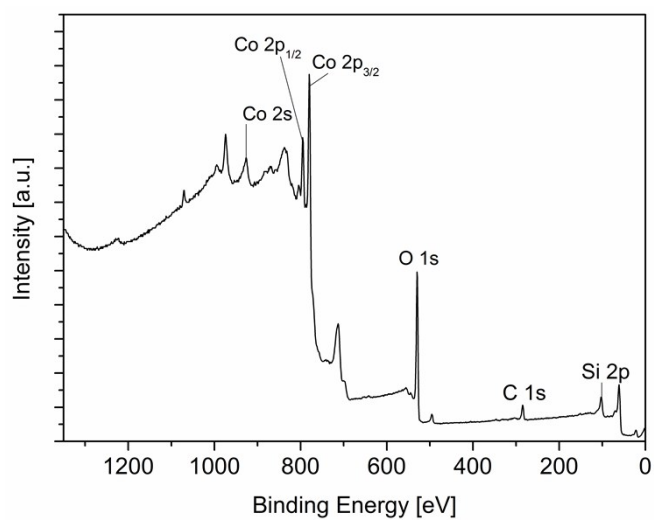


Figure S14. XPS survey spectra of the cobalt oxide thin layer deposited on a glass substrate using a 0.8 M precursor concentration of **4**.

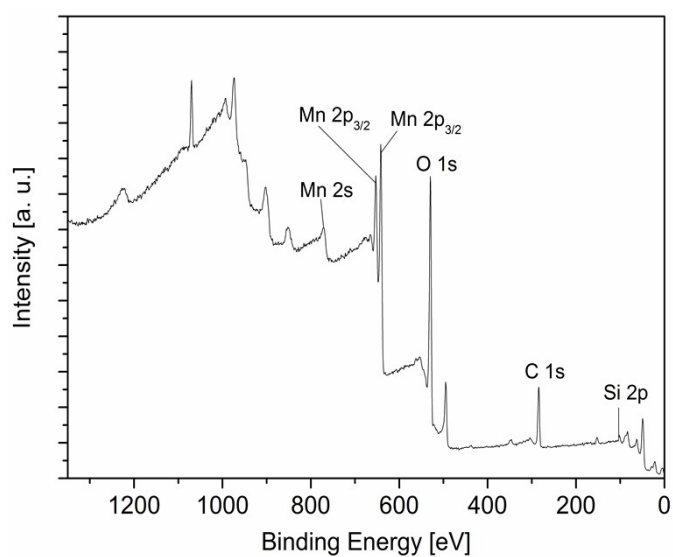


Figure S15. XPS survey spectra of the manganese oxide thin layer deposited on a glass substrate using a 0.8 M precursor concentration of **5**.